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U.S. PATENT DOCUMENTS									
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A		2-27660	06/19/90	Japan			120	√	
	•	7-234511	09/05/95	Japan	Time		ABS		
	,	8-259626	10/08/96	Japan			ABS		
		10-171122	06/26/98	Japan			ABS		
W	-	7-252324	10/03/95	Japan			ABS		
·		OTHER DOCUME	ENTS (Includi	ling Author, Title, Date, Per	rtinent Pages, Etc.)	1/1001		
(A)	Donald C. Hofer, et al., "193 nm Photoresist R&D: The Risk & Challenge", Journal of Photopolymer Science and Technology, Vol. 9, No. 3, pp. 387-397, May 16, 1996.								
M	Hiroshi Ito, et al., "Applications of Photoinitiators to the Design of Resists for Semiconductor Manufacturing", American Chemical Society Symposium Series, Vol. 242, pp. 11-23, 1984.								
EXAMINER	DATE CONSIDERED 11-19-01								

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

ATTY DOCKET NO. SERIAL NO. NEC99P156-ms Not Yet Assigned INFORMATION DISCLOSURE CITATION APPLICANT(S) Maeda, et al. (Use several sheets if necessary) FILING DATE GROUP Not Yet Assigned **Concurrently Herewith U.S. PATENT DOCUMENTS** FILING DATE *EXAMINER CLASS SUBCLASS DOCUMENT NUMBER DATE NAME IF APPROPRIATE INITIAL **FOREIGN PATENT DOCUMENTS** TRANSLATION DOCUMENT NUMBER DATE COUNTRY CLASS SUBCLASS YES NO WĀ 01/31/95 7-28237 Japan 7-199467 08/04/95 Japan 7-219231 08/18/95 Japan 10-3169 01/06/98 Japan ABS 01/19/96 8-15865 Japan

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

Takechi, et al., "Alicyclic Polymer for ArF and KrF Excimer Resist Based on Chemical Amplification", Journal of Photopolymer Science and Technology, Vol. 5, No. 3, pp. 439-446, 1992.

R.D. Allen, et al., "Resolution and Etch Resistance of a Family of 193 nm Positive Resists", Journal of Photopolymer Science and Technology, Vol. 8, No. 4, pp. 623-636,1995.

EXAMINER PASAL

DATE CONSIDERED

1-19-01

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION

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ATTY DOCKET NO. NEC99P156-ms	SERIAL NO. Not Yet Assigned
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	DOCUMENT NUMBER	DATE		COUNTRY	CLASS	SUBCLASS	YES	NO
RA	5-134416	05/28/93	Japan				:	/
418	8-335603	12/17/96	Japan				ABS	
	OTHER DOCUM	MENTS (Includ	ding Autho	r, Title, Date, Pert	inent Pages, E	tc.)	ology. Vol. 9	9. No. 3
W	R.D. Allen, et al., "Pi pp. 456-474, 1996.							
CB	J.V. Crivello, et al., " Arylation of Sulfides 3055-3058, 1978.	A New Preparat and Selenides w	ion of Tria ith Diarylio	rylsulfonium and -sel donium Salts", Jouri	enonium Salts vi nal of the Organi	a the Copper (I ic Chemistry, Vo	I)-Catalyze ol. 43, No. 1	d 15, pp.
EXAMINER	RASLA			DATE CONSIDERE	11-19-01			
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*EXAMINER		OTHER DOCUMENTS (Including Author, Title, Date, Pertin	ent Pages, Etc.)	
M		F. M. Houlihan, et al., "The Synthesis, Characterization and I Photo-Acid Generators with Improved Resistance to Post Exp	Lithography of x-Substitut osure Bake", SPIE Proced	ted 2-Nitrobenzyl Arylsulfonate edign, Vol. 2195, pp. 137-151, 1994.
		Takumi Ueno, et al., "Chemical Amplification Positive Resist Proceeding of PME '89, Kodansha, pp. 413-424, 1990.	Systems Using Novel Sulf	onates as Acid Generators",
		H.B. Henbest, et al., "Aspects of Stereochemistry", J. Chem. S	Soc., pp. 221-226, 1959.	
RA		S. Bechmann, et al., "Zur Kenntnis der bei der Hydratisierun Lactone", Chem. Ber., Vol. 94, pp. 48-58, 1961.	g von Bicyclo-[1.2.2]-hept	en-carbonsauren entstehenden
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